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Sen Ullrich

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# INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

F06-436-US

Application Number

Not Yet Assigned

Applicant(s)

Mineo HIRAMATSU and Masaru HORI

Filing Date

Concurrently Herewith

Group Art Unit

Not Yet Assigned

## U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

## U.S. PATENT APPLICATION PUBLICATIONS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

## FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO
		11-67490	03/09/1999	Japan			ABS	
		2003-173980	06/26/2003	Japan			ABS	
		2001-81570	03/27/2001	Japan			ABS	

## OTHER DOCUMENTS

(Including Author, Title, Date, Pertinent Pages, Etc.)

		Mineo HIRAMATSU, et al., "Fabrication of Carbon Nanowalls Using RF Plasma CVD" Abstracts for The 16th Symposium on Plasma Science for Materials, pp. 20, A2-4.
		Mineo HIRAMATSU, et al., "Fabrication of vertically aligned carbon nanowalls using capacitively coupled plasma-enhanced chemical vapor deposition assisted by hydrogen radical injection", Applied Physics Letters, Vol. 84, No. 23, pp. 4708-4710 (2004).

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.